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Approved for use through 10/31/2002. OMB 0651-0031

U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

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		Application Number	09/296,835	
TRANSMITTAL	•	Filing Date	April 22, 1999	
FORM		First Named Inventor	Ronald A. Weimer	
° (to be used for all correspondence after initial	filing)	Group Art Unit	2813	
•		Examiner Name	Erik Kielin	
Total Number of Pages in This Submission 7		Attorney Docket Number	M4065.0319/P319	

ENCLOSURES (check all that apply)									
Fee Transm	ittal Form	Assignment (for an Ap	ent Papers olication)	After Allowance Communication to Group					
Fee A	ttached	Drawing(	s)	Appeal Communication to Board of Appeals and Interferences					
X Amendment	/Reply	Licensing	g-related Papers	Appeal Communication to Group (Appeal Notice, Brief, Reply Brief)					
X After F	Final	Petition		Proprietary Information					
Affida	vits/declaration(s)	Petition t Application	o Convert to a Provisional on	Status Letter					
Extension of Time Request			Attorney, Revocation f Correspondence Address	X Other Enclosure(s) (please identify below)					
Express Abandonment Request		Terminal	Disclaimer	Amendment Transmittal     Amendment and Response					
Information Disclosure Statement		Request for Refund		to final Office Action					
Certified Copy of Priority Document(s)		CD, Number of CD(s)		MAY -					
Response to Missing Parts/ Incomplete Application		Remarks	M* 12	-8 2003 MAIL ROOM					
Response to Missing Parts under 37 CFR 1.52 or 1.53			•	<b>2003</b> IL RO					
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	SIGNA	TURE OF APP	LICANT, ATTORNEY, OR A	GENT					
Firm or Individual Name	DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP Thomas J. D'Amigo, #28,37)								
Signature	Jan 1								
Date	May 5, 2003								

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## AMENDMENT TRANSMITTAL LETTER Application No. Filing Date Example 122 1999 Fril 22 1999 Fril 22 1999

Docket No. M4065.0319/P319

Application No.Filing DateExaminerArt Unit09/296,835April 22, 1999Erik Kielin2813

Applicant(s): Ronald A. Weimer, et al.

FABRICATION OF DRAM AND OTHER SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

## TO THE COMMISSIONER FOR PATENTS

**CLAIMS AS AMENDED** 

Number

**Extra Claims** 

Present

Rate

Transmitted herewith is an amendment in the above-identified application.

Highest

Number Previously

Paid

The fee has been calculated and is transmitted as shown below.

Claims

Remaining

After Amendment

DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP

Total Claims	14	-	40	=		X	0.00
Independent Claims	7	-	8	=		x	0.00
Multiple Depend	lent Claims (c	heck if	appli	cabl	e)		
Other fee (pleas	e specify):						
TOTAL ADDIT	IONAL FEE I	FOR TI	IIS A	ME	NDMENT:		
x Large Entity						Small Entit	ty
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Payment by	credit card.	Form P	TO-2	2038	is attached.		
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<u> </u>	h!	>				Dated:	May 5, 2003⊖
Thomas J. D'Ar							28
Attorney Reg. N	No.: 28,371						<u> </u>

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Washington, DC 20037-1526





Docket No.: M4065.0319/P319
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: Ronald A. Weimer, et al.

Application No.: 09/296,835

Filed: April 22, 1999

For: FABRICATION OF DRAM AND OTHER SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

Group Art Unit: 2813

Examiner: Erik Kielin

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## AMENDMENT UNDER 37 CFR § 1.116

ATTN: BOX AF

Commissioner for Patents Washington, DC 20231

Dear Sir:

Responsive to the Office Action dated February 4, 2003, please amend the above-captioned U.S. Patent application as follows:

## IN THE CLAIMS:

Please rewrite claims 8 and 42-47 as follows:

8. (six times amended) A method of fabricating a semiconductor device

comprising:

depositing an oxygen-deficient dielectric film having a dielectric constant of at least about 25 over an underlying layer;

subjecting the dielectric film to a wet oxidation with steam process provided by

1606649 v1; YFP501!.DOC

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